Supporting Information (SI)

Surface Modification of Polylactic Acid using Photo-activated Chlorine Dioxide Process: Surface Properties and Dissimilar Adhesion

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1. Supporting figures

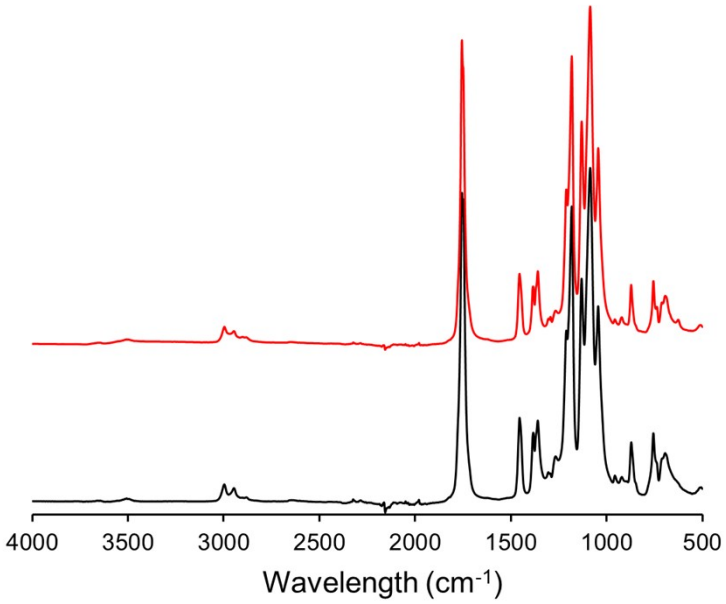

Fig. S1 FT-IR spectra of the PLA samples: untreated (black), and oxidized under 80 °C, 10min (red).

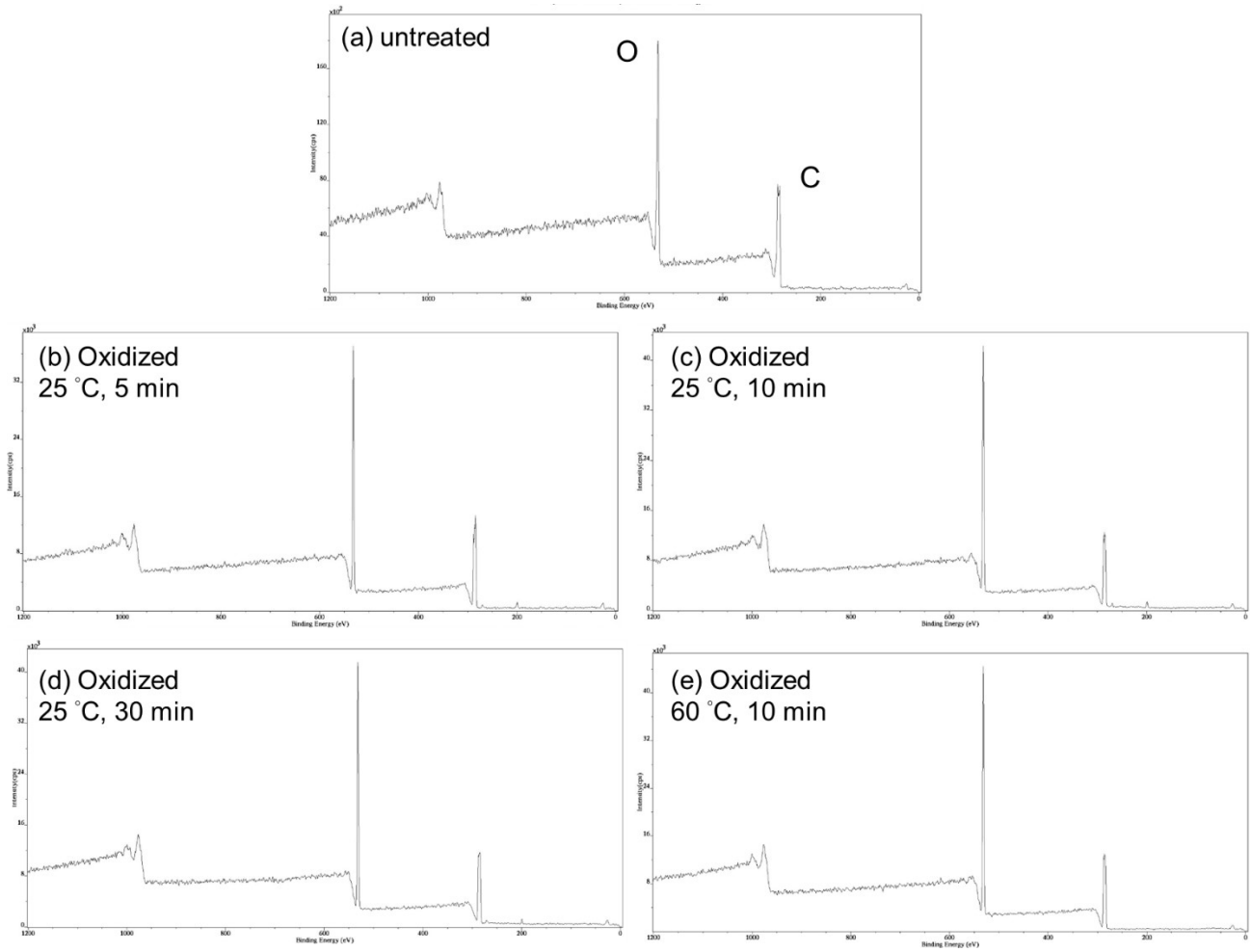

Fig. S2 Wide XPS spectra of (a) untreated PLA; (b) PLA oxidized under 25 °C, 5min; (c) PLA oxidized under 25 °C, 10min; (d) PLA oxidized under 25 °C, 30 min; (e) PLA oxidized under 60 °C, 10min.

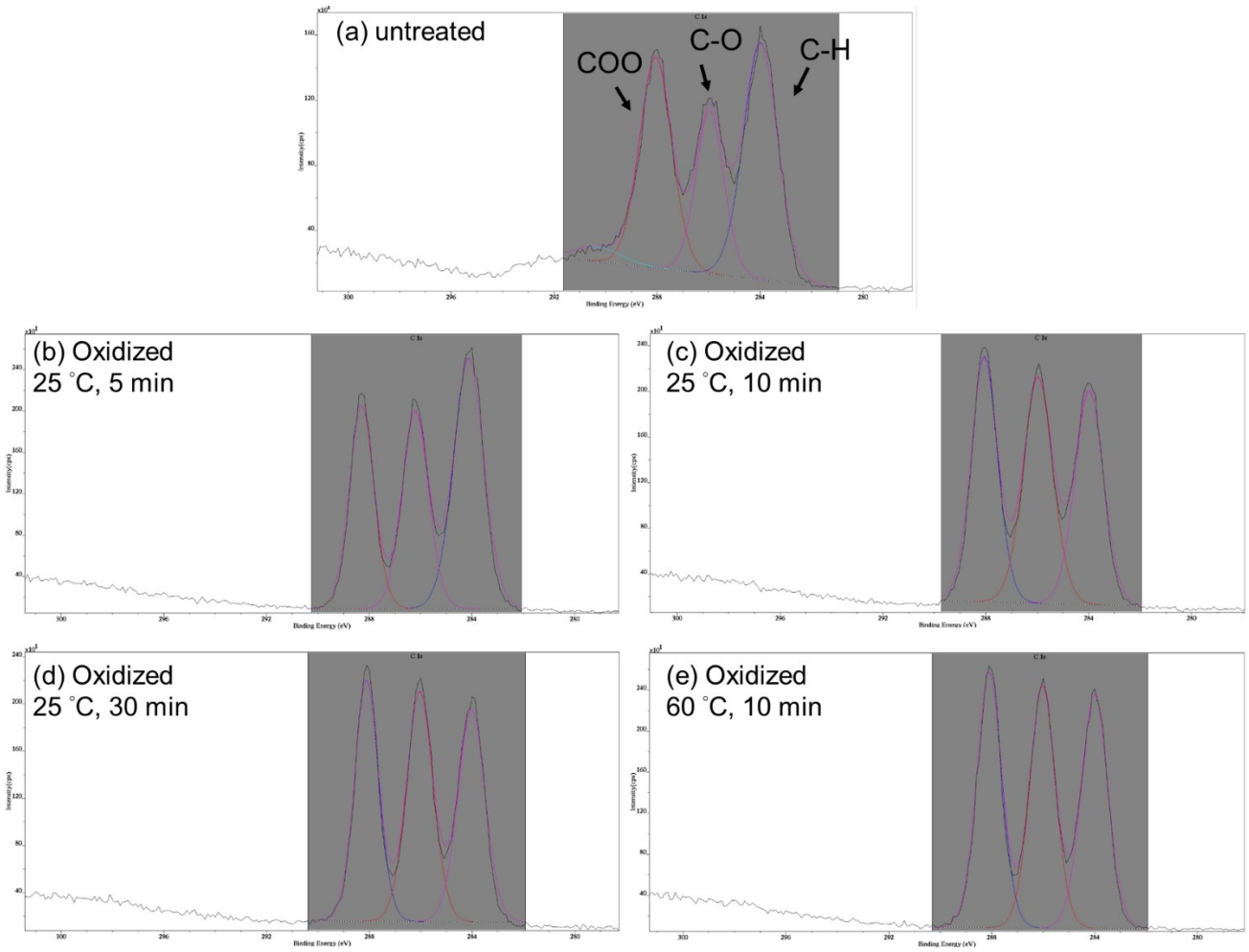

Fig. S3 C1s XPS spectra of (a) untreated PLA; (b) PLA oxidized under 25 °C, 5min; (c) PLA oxidized under 25 °C, 10min; (d) PLA oxidized under 25 °C, 30 min; (e) PLA oxidized under 60 °C, 10min.